

## 5 CLAIMS:

1. A method for controlling a moisture level of a material to be used in a cleanroom, the method comprising;
  - 10 placing the material in a wetting chamber;
  - applying a cleaning solution to the material; and
  - controlling a saturation level of the cleaning solution in the material.
2. The method of claim 1 wherein controlling the saturation level comprises controlling the applying of cleaning solution to the material as a function 15 of electrical conductivity of the material.
3. The method of claim 1 wherein controlling the saturation level comprises controlling the applying of cleaning solution to the material as a function of mass of the material.
- 20 4. The method of claim 1 wherein controlling the saturation level comprises controlling the applying of cleaning solution to the material as a function of time.
- 25 5. The method of claim 1 wherein controlling saturation level comprises applying pressure to the material to reduce the saturation level of the material to a target saturation level.
- 30 6. A device for moistening a material used in a cleanroom to a target saturation level, the device comprising;
  - a chamber;
  - 35 a rack positioned in the chamber for holding the material;

5                   a liquid supply of a liquid;  
an applicator in the chamber for applying the liquid to the material;  
a delivery system for delivering the liquid from the supply to the  
applicator; and  
10                 a control system for controlling the amount of liquid applied to the  
material based on a parameter related to the target saturation  
level of the material.

7.                 The device of claim 6 wherein the control system controls the  
amount of liquid dispensed to the material as a function of electrical conductivity of  
15                 the material.

8.                 The device of claim 6 wherein the control system controls the  
amount of liquid dispensed to the material as a function in mass of the material.

20 9.                 The device of claim 6 wherein the control system controls the  
amount of liquid dispensed to the material as a function of a time duration.

10.                The device of claim 6 wherein the rack is centrally positioned within  
the chamber.

25 11.               The device of claim 6 wherein the applicator includes a pump for  
pumping the liquid under pressure and a nozzle for applying the liquid.

30 12.               The device of claim 6 wherein the control system includes a pump  
control for controlling the amount of liquid applied to the material.

5 13. The device of claim 6 wherein the control system includes a user interface for providing a user input signal representing the target saturation level.

14. The device of claim 6 wherein the control system includes a feedback sensor for providing a feedback signal representing the parameter.

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15. The device of claim 6 wherein the control system includes a shut off sensor for providing a signal to the control system to disengage from the application of liquid to the material when the chamber is in an open position.

15 16. The device of claim 6 wherein the chamber has a drain for draining excess liquid.

17. The device of claim 16 wherein the drain leads to a liquid collection system.

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18. A device for moistening a material used in a cleanroom, the device comprising:

a rack for holding the material;

an applicator spaced from and directed toward the rack for applying

25 a liquid to the material; and

a control system for controlling application of liquid to the material based on a desired saturation level of the material.

19. The device of claim 18 wherein the applicator is movable with  
30 respect to the rack.

5        20.        The device of claim 18 wherein the applicator comprises a plurality  
of nozzles.

21.        The device of claim 18 wherein the plurality of nozzles has a first set  
of nozzles positioned above the rack and a second set of nozzles positioned below  
10        the rack.

22.        The device of claim 18 wherein the control system controls the  
amount of liquid dispensed to the material as a function of conductivity of the  
material.

15        23.        The device of claim 18 wherein the control system controls the  
amount of liquid dispensed to the material as a function of mass of the material.

24.        The device of claim 18 wherein the control system controls the  
20        amount of liquid dispensed to the material as a function of time.

25        25.        The device of claim 18 wherein the machine has a drainage and  
collection system.

26.        A device for moistening a material used in a cleanroom to a desired  
saturation level, the device comprising:

30        a chamber;  
              a rack positioned in the chamber for holding the material;  
              an applicator for applying liquid to the material;  
              a user interface for providing a user input signal;  
              a feedback system for providing a feedback signal which is a  
              function of the saturation level of the material; and

5           a control system for controlling the amount of liquid applied to the  
material as a function of the user input signal and the  
feedback signal.

27.           The device of claim 26 further comprising a pressure applicator  
10          for applying pressure to the material to reduce liquid content of the material.